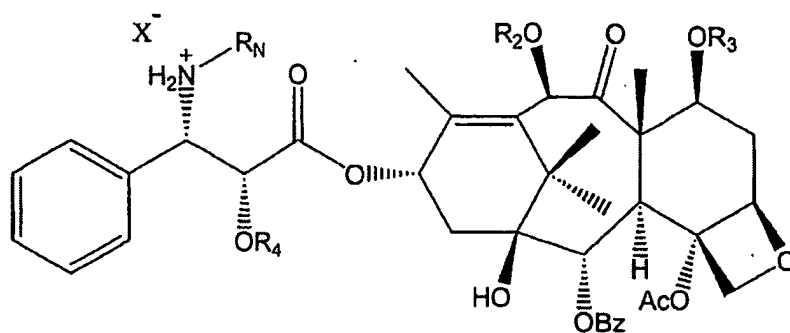


Amendments to the Claims:

1. (Currently amended) A ~~compound~~ method for ~~producing~~ forming ~~[[of]]~~ a taxane or precursor or analog thereof from a raw material, the raw material comprising a compound represented by the formula below:



wherein, R₂ is H, Ac or a protecting group;

R₃ is H, xylosyl or protecting group;

R₄ is H or protecting group;

R_N is H or an alkyl group; and

X= deprotonated sulfuric acid or deprotonated sulfur containing acid;

deprotonated nitric acid or other nitrogen containing acid; deprotonated carboxylic acid, except trifluoro acetic acid; deprotonated phosphoric acid or any phosphorus containing acid; deprotonated tartaric acid; deprotonated p-toluene sulfonic acid; or deprotonated picric acid; and

wherein said taxane or precursor or analog thereof is in a solid, purified form;

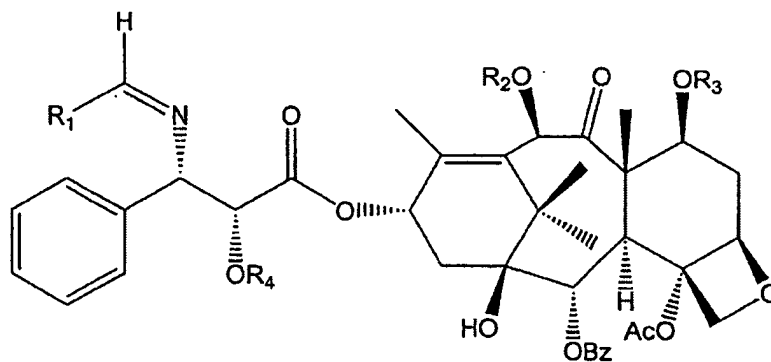
the method comprising benzoylating the raw material with a benzoylation solution comprising a benzoylating agent and a buffer such that the pH of the benzoylation solution is about 4 to about 6.

2. (Currently amended) The ~~compound~~ method of claim 1, ~~in solid form~~ wherein the buffer comprises a phosphate buffer.

3. (Currently amended) The ~~compound~~ method of claim 2, ~~in solid substantially purified form~~ wherein the phosphate buffer is of about pH 7.
4. (Currently amended) The ~~compound~~ method of claim 1, wherein R₂ is Ac and R₃ is H.
5. (Currently amended) The ~~compound~~ method of claim 1, wherein R₂ is H and R₃ is H.
6. (Currently amended) The ~~compound~~ method of claim 1, wherein R₂ is Ac and R₃ is xylosyl.
7. (Currently amended) The ~~compound~~ method of claim 1, wherein R₂ is H and R₃ is xylosyl.
8. (Currently amended) The ~~compound~~ method of claim 1, wherein R₂, R₃ and R₄ is the protecting group selected from the group consisting of triethylsilyl, trimethylsilyl, trichloroethoxycarbonyl ~~[[or]]~~ and ethoxyethyl ether.
9. (Currently amended) The ~~compound~~ method of claim 1, wherein R₃ and R₄ is a protecting group selected from the group consisting of triethylsilyl, triethylsilyl, trichloroethoxycarbonyl and ethoxyethyl ether.
10. (Currently amended) The ~~compound~~ method of claim 1, wherein R₃ and R₄ is trimethylsilyl.
11. (Currently amended) The ~~compound~~ method of claim 1, wherein R₄ is a protecting group selected from the group consisting of triethylsilyl, triethylsilyl, trichloroethoxycarbonyl and ethoxyethyl ether.

12. (Currently amended) The ~~compound~~ method of claim 1, wherein R₄ is trimethylsilyl.

13. (Currently amended) A method of forming a taxane amine or salt comprising the steps of: (i) contacting a taxane imine according to the formula below with a protic solvent; and ~~(ii) contacting a taxane imine with a sulphate-containing acid;~~
~~said taxane imine having the formula:~~



wherein, R₁ =alkyl, aryl, carbonyl or ether group;

R₂ =H, alkyl, aryl, ester, ether or protecting group;

R₃ =H, alkyl, aryl, ether, ester, xylosyl, or protecting group;

R₄ =H or protecting group;

(ii) contacting the taxane imine with an acid useful to effect hydrolysis of the imine; and

(iii) isolating a solid, purified taxane amine or salt by adding a solvent that is less polar than said protic solvent.

14 – 61. (Canceled)

62. (Currently amended) The ~~compound~~ method of claim 1, wherein X is a deprotonated nitric acid or other nitrogen containing acids.

63. (Currently amended) The ~~compound~~ method of claim 1, wherein X is a deprotonated sulfur containing acid.

64. (Currently amended) The ~~compound~~ method of claim 1, wherein X is a deprotonated carboxcyclic acid, except trifluoro acetic acid.

65. (Currently amended) The ~~compound~~ method of claim 1, wherein X is deprotonated phosphoric acid or any phosphorus containing acid.

66. (Currently amended) The ~~compound~~ method of claim 1, wherein X is deprotonated tartaric acid.

67. (Currently amended) The ~~compound~~ method of claim 1, wherein X is deprotonated perchloric acid.

68. (Currently amended) The ~~compound~~ method of claim 1, wherein X is deprotonated p-tolulene sulfonic acid, ~~and said compound is in solid form.~~

69. (Currently amended) The ~~compound~~ method of claim 1, wherein X is a deprotonated picric acid.

70 – 100 (Canceled)

101. (Currently amended) The ~~compound~~ method of claim 1, wherein the ~~compound is for the production of~~ formed taxane is taxol A.

102. (Currently amended) The ~~compound~~ method of claim 1, wherein the ~~compound is for the production of~~ formed taxane is taxol B.

103. (Currently amended) The ~~compound~~ method of claim 1, wherein the

~~compound is for the production of~~ formed taxane is taxol C.

104. (Currently amended) The ~~compound~~ method of claim 1, wherein the ~~compound is for the production of~~ formed taxane is taxol D.

105. (Currently amended) The ~~compound~~ method of claim 1, wherein the ~~compound is for the production of~~ formed taxane is taxol E.

106. (Currently amended) The ~~compound~~ method of claim 1, wherein the ~~compound is for the production of~~ formed taxane is taxol F.

107. (Currently amended) The ~~compound~~ method of claim 1, wherein the ~~compound is for the production of~~ formed taxane is taxol G.

108. (Currently amended) The ~~compound~~ method of claim 1, wherein the ~~compound is for the production of~~ formed taxane is Docetaxel.

109. (Currently amended) The ~~compound~~ method of claim 1, wherein the ~~compound is for the production of~~ formed taxane is Nonataxel.

110-112. (Canceled)

113. (New) The method of claim 1, wherein the method further comprises contacting the benzylation solution with an amine containing compound after the benzylation reaction is complete.

114. (New) The method of claim 113, wherein the amine containing compound comprises a primary amine.

115. (New) The method of claim 113, wherein the amine containing compound

comprises ammonium hydroxide.

116. (New) The method of claim 113, wherein the method further comprises isolating an organic layer and washing the organic layer with a composition comprising an amine containing compound.

117. (New) The method of claim 13, wherein the solvent used in step (iii) is selected from the group consisting of methyl tert-butyl ether, dichloromethane, heptane, hexane, toluene, and trifluorotoluene.

118. (New) The method of claim 13, wherein the acid used in step (ii) is selected from the group consisting of sulfuric acid, nitric acid, phosphoric acid, tartaric acid, p-toluene sulfonic acid, picric acid, and combinations thereof.